



December 12, 2003

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/664,210 09/17/03 |

Yong Meng Lee et al.

METHOD OF FORMING DOUBLE-GATE  
SEMICONDUCTOR-ON-INSULATOR (SOI)  
TRANSISTORS

#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
mail in an envelope addressed to: Commissioner for Patents,  
P.O. Box 1450, Alexandria, VA 22313-1450, on December 19, 2003.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

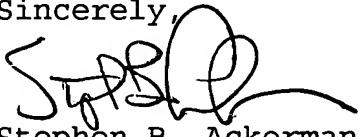
A handwritten signature in black ink that appears to read "Stephen B. Ackerman" followed by the date "12/19/03".

U.S. Patent 6,451,656 to Yu et al., "CMOS Inverter Configured From Double Gate MOSFET and Method of Fabricating Same," describes a double-gate transistor on semiconductor-on-insulator (SOI).

U.S. Patent 6,413,802 to Hu et al., "FinFET Transistor Structures Having a Double Gate Channel Extending Vertically From a Substrate and Methods of Manufacture," describes a double-gate FinFET on semiconductor-on-insulator (SOI).

U.S. Patent 6,365,465 to Chan et al., "Self-Aligned Double-Gate MOSFET by Selective Epitaxy and Silicon Wafer Bonding Techniques," describes a process for a double gate MOSFET on semiconductor-on insulator (SOI).

U.S. Patent 6,396,108 to Krivokapic et al., "Self-Aligned Double Gate Silicon-On-Insulator (SOI) Device," describes a process for a double gate MOSFET on semiconductor-on-insulator (SOI).

Sincerely,  
  
Stephen B. Ackerman,  
Reg. No. 37761

**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.